

Fig. 1

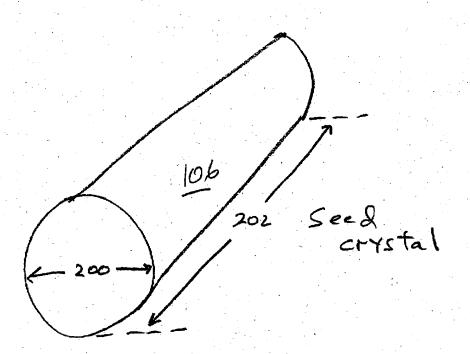


Fig. 2

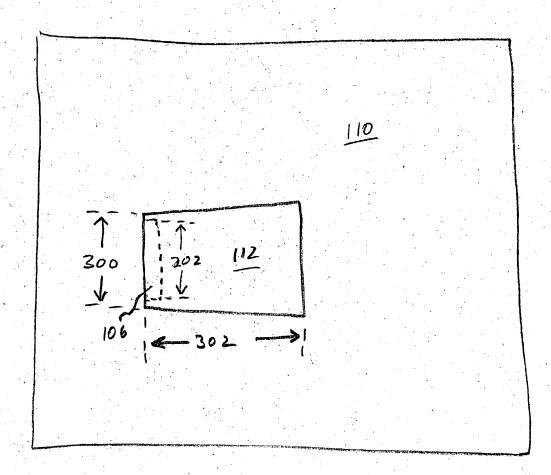


Fig. 3

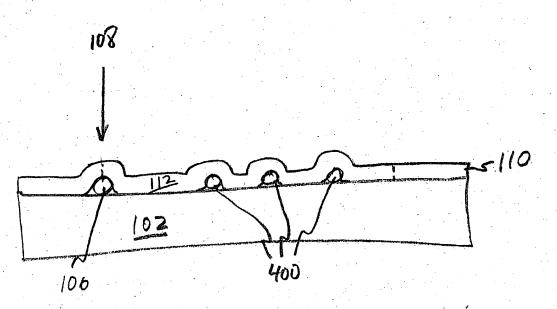
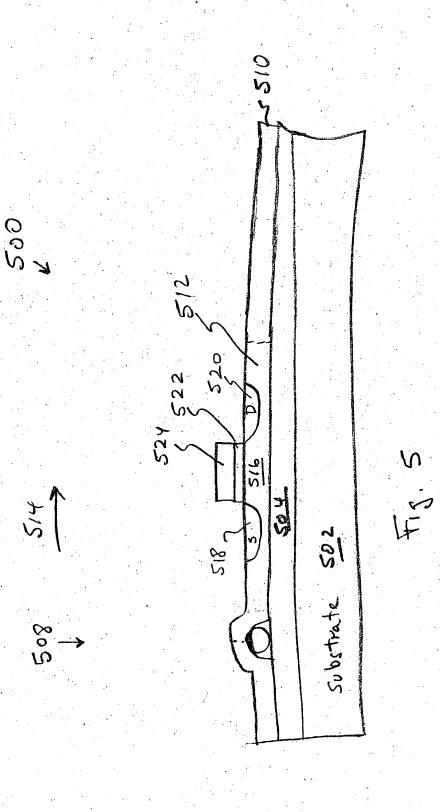
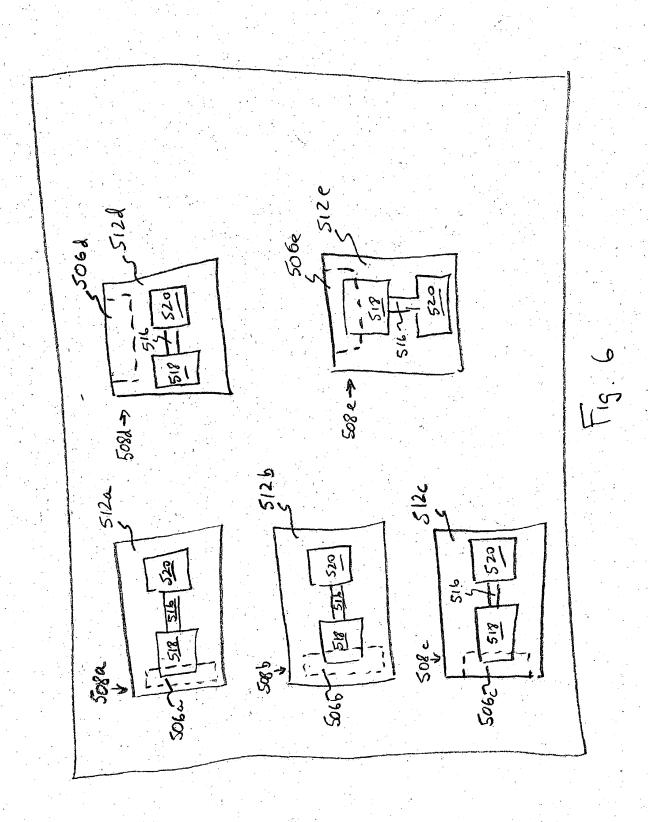
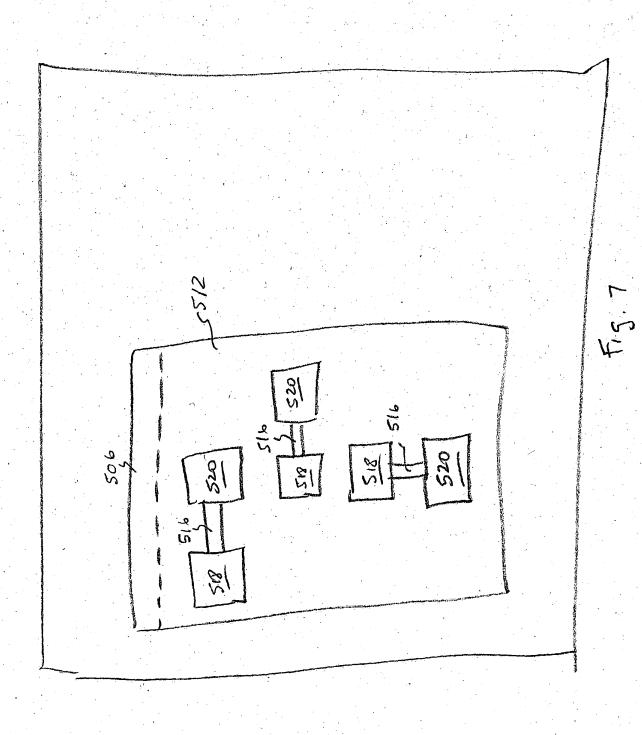


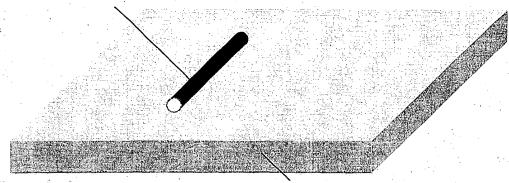
Fig. 4





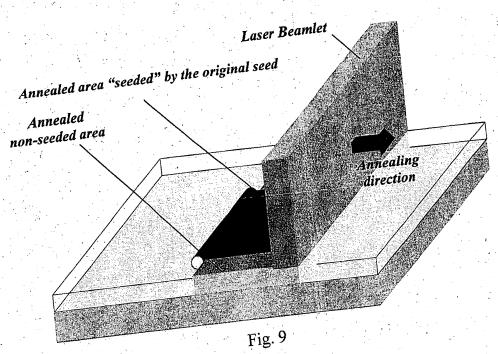


## Semiconductor "seed" (i.e. Si nanowire: ~10nm dia, ~100um length)



Substrate (w/ or w/o additional coatings)

Fig. 8



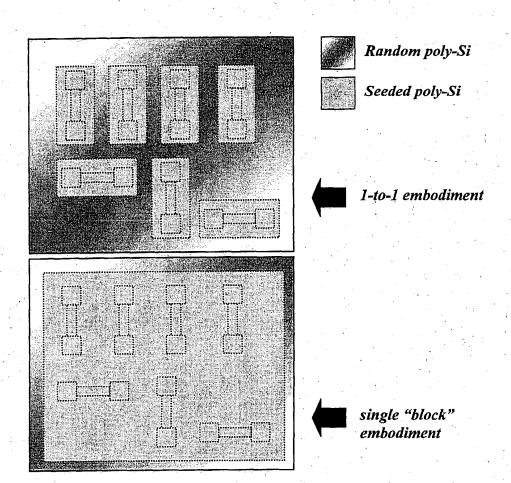


Fig. 10

START Julion Forming substrate = 1102 Forming insulator film \$ 1103 torming single-crystal seed Forming amorphous film & 1106 annealing 5 1108 5/110 forming single-crystal domain forming pixel areas

Fig. 11